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	APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
	10/617,337	07/10/2003	Jennifer Samproni	036249-5006	5011	
	9629 , 7:	590 11/29/2006		EXAMINER		
		EWIS & BOCKIUS LLP		NOGUEROLA, ALE	NOGUEROLA, ALEXANDER STEPHAN	
	1111 PENNSYLVANIA AVENUE NW WASHINGTON, DC 20004			ART UNIT	PAPER NUMBER	
			1753			
				DATE MAILED: 11/29/2006		

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)				
		10/617,337	SAMPRONI, JEN	SAMPRONI, JENNIFER			
	Office Action Summary	Examiner	Art Unit				
		ALEX NOGUEROLA	1753				
Period fo	The MAILING DATE of this communicator Reply	ion appears on the cover she	et with the correspondence a	ddress			
WHIC - Exte after - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR CHEVER IS LONGER, FROM THE MAIL nsions of time may be available under the provisions of 37 SIX (6) MONTHS from the mailing date of this communic period for reply is specified above, the maximum statutor to reply within the set or extended period for reply will, reply received by the Office later than three months after the patent term adjustment. See 37 CFR 1.704(b).	ING DATE OF THIS COMM CFR 1.136(a). In no event, however, mation.  y period will apply and will expire SIX (6 by statute, cause the application to beco	UNICATION.  nay a reply be timely filed  ) MONTHS from the mailing date of this me ABANDONED (35 U.S.C. § 133).				
Status							
1)	Responsive to communication(s) filed o	n .					
2a)	·	This action is non-final.					
3)□		_	matters, prosecution as to th	ne merits is			
,—	3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Dispositi	on of Claims	,	,				
	Claim(s) 1-21 is/are pending in the appl	cation					
	4a) Of the above claim(s) is/are w		•				
	Claim(s) is/are allowed.	mindration obtained	•				
· · · · · · · · · · · · · · · · · · ·	6)⊠ Claim(s) <u>1-9,11,12 and 16-19</u> is/are rejected.						
	7)⊠ Claim(s) <u>1-9,11,12 and 10-19</u> is/are rejected. 7)⊠ Claim(s) <u>10,13-15,20 and 21</u> is/are objected to.						
	Claim(s) are subject to restriction	•	<b>t</b>				
		androi oloolloii requirement	•				
	on Papers						
	The specification is objected to by the Ex						
10)	[0] The drawing(s) filed on is/are: a) □ accepted or b) □ objected to by the Examiner.						
	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
440	Replacement drawing sheet(s) including the			• •			
11)	The oath or declaration is objected to by	the Examiner. Note the attached	ched Office Action or form P	TO-152.			
Priority u	inder 35 U.S.C. § 119						
	12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of:						
	1. Certified copies of the priority doc	uments have been received.					
	2. Certified copies of the priority doc	uments have been received	in Application No				
	3. Copies of the certified copies of the	e priority documents have b	een received in this National	l Stage			
	application from the International	Bureau (PCT Rule 17.2(a)).		-			
* See the attached detailed Office action for a list of the certified copies not received.							
Attachment	(s)						
	e of References Cited (PTO-892)	4) 🔲 Intervi	iew Summary (PTO-413)				
	e of Draftsperson's Patent Drawing Review (PTO-S nation Disclosure Statement(s) (PTO/SB/08)		No(s)/Mail Date  e of Informal Patent Application				
Paper	No(s)/Mail Date <u>10/27/2003</u> .		: <u>IDS of12/23/2005</u> .				

## **DETAILED ACTION**

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## Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. The factual inquiries set forth in *Graham* v. *John Deere Co.*, 383 U.S. 1, 148 USPQ 459 (1966), that are applied for establishing a background for determining obviousness under 35 U.S.C. 103(a) are summarized as follows:
  - 1. Determining the scope and contents of the prior art.
  - 2. Ascertaining the differences between the prior art and the claims at issue.
  - 3. Resolving the level of ordinary skill in the pertinent art.
  - 4. Considering objective evidence present in the application indicating obviousness or nonobviousness.
- 3. Claims 1-9, 11, 12, 16, 17, and 19 are rejected under 35 U.S.C. 103(a) as being unpatentable over the English language Translation of Patent Application Public Disclosure No. 05-60724 provided by Applicant ("No. 05-60724") in view of Ghahramani et al. (US 6,340,741 B1) ("Ghahramani").

Addressing claim 1, No. 05-60724 discloses a chloride selective electrode membrane comprising a

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polymeric matrix wherein the matrix comprises:

an epoxy resin; and

a polyamide as an amine agent. See claim 1 and paragraph [0006] of No. 05-60724.

No. 05-60724 does not mention providing the agent in stoichiometric excess. However, No. 05-60724 does teach that varying the ratio of polythiol epoxy resin to polyamide epoxy resin in the polymeric matrix will alter the ion selectivity. In particular, a larger presence of polyamide epoxy resin than polythiol epoxy resin will make the polymeric matrix less susceptible to interference from hydrophilic ions. A larger presence of polythiol epoxy resin than polyamide epoxy resin will make the polymeric matrix less susceptible to interference from lipophilc ions. See paragraphs [0012] to [0014]. Thus, providing a much larger relative amount of polyamide epoxy resin to polythiol epoxy resin and thus a stoichiometric excess of agent is just a matter of optimizing the polymeric matrix to be selective against lipohilic ions.

Alternatively, It would have been obvious to one with ordinary skill in the art at the time of a stoichiometric excess of agent because as taught by Ghahramani, which discloses a membrane for use in chloride-sensitive electrodes, the membrane comprising an epoxy resin with an amino curing agent, this will result in a high degree of selectivity. See the abstract; col. 03:23-30 and col. 04:61-67 in Ghahramani.

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Addressing claim 2, for the additional limitation of this claim see in No. 05-60724 claim 1 and paragraph [0006].

Addressing claims 3-9, the additional limitations of these claims are product-byprocess limitations. Although particular ingredients are specified, it is not clear how the product is limited to a subset of polyamides as the reaction steps are not also specified. Thus, claims 3-9 do not appear to further limit 2 from which they depend directly or indirectly.

Addressing claim 11, the additional limitation of this claim is a product-by-process limitation. Although particular ingredients are specified, it is not clear how the epoxy resin is further limited as the reaction steps are not also specified.

Addressing claims 12 and 19, as stated in the rejection of claim 1 the amount of amine agent is just a matter of optimizing the ratio of polythiol epoxy resin to polyamide epoxy in the polymeric resin, that is, the desired selectivity to hydrophilic ions versus lipophilic ions. Alternatively, note that Ghahramani discloses an upper limit of 150% amine agent, which is a shared end point with the claimed "at least 150%".

Addressing claim 16, No. 05-60724 discloses a chloride selective electrode comprising a chloride selective electrode membrane comprising a polymeric matrix wherein the matrix comprises:

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an epoxy resin; and

a polyamide as an amine agent. See claim 1 and paragraph [0006] of No. 05-60724.

No. 05-60724 does not mention providing the agent in stoichiometric excess. However, No. 05-60724 does teach that varying the ratio of polythiol epoxy resin to polyamide epoxy resin in the polymeric matrix will alter the ion selectivity. In particular, a larger presence of polyamide epoxy resin than polythiol epoxy resin will make the polymeric matrix less susceptible to interference from hydrophilic ions. A larger presence of polythiol epoxy resin than polyamide epoxy resin will make the polymeric matrix less susceptible to interference from lipophilc ions. See paragraphs [0012] to [0014]. Thus, providing a much larger relative amount of polyamide epoxy resin to polythiol epoxy resin and thus a stoichiometric excess of agent is just a matter of optimizing the polymeric matrix to be selective against lipohilic ions.

Alternatively, It would have been obvious to one with ordinary skill in the art at the time of a stoichiometric excess of agent because as taught by Ghahramani, which discloses a membrane for use in chloride-sensitive electrodes, the membrane comprising an epoxy resin with an amino curing agent, this will result in a high degree of selectivity. See the abstract; col. 03:23-30 and col. 04:61-67 in Ghahramani.

Addressing claim 17, the additional limitation of this claim is met by paragraph [0032] of No. 05-60724, which discloses determining the chloride ion concentration at which the potential difference deviates.

4. Claim 18 is rejected under 35 U.S.C. 103(a) as being unpatentable over Craig et al. (US 6,015,480) ("Craig") in view of the English language Translation of Patent Application Public Disclosure No. 05-60724 provided by Applicant ("No. 05-60724").

Craig discloses a sensor assembly for deterring chloride ion in a test liquid, comprising:

an electrically insulated substrate (12) having a surface with a reference electrode (10R) formed thereon (Figure 3), whereon the chloride selective electrode comprises

a chloride selective electrode membrane comprising a polymeric matrix (col. 08:47-56);

means positioned on the surface of the substrate defining a reference flow channel ((34R) – col. 06:05-7) and a sensor flow channel ((34M) – col. 06:08-09);

the reference flow channel having means for passing reference liquids over the reference electrode (col. 06:19-22);

the sensor flow channel having means for passing test liquid over the sensor electrode (col. 06:19-22); and the reference and sensor flow channels defining a common outlet for removing liquids from the assembly (col. 05:40-42).

Craig does not mention whether the polymer matrix comprises

an epoxy resin; and

an amine selected from the group consisting of polyamide, amidoamines and mixtures thereof, wherein the amine is present in stoichiometric excess.

No. 05-60724 discloses a chloride selective electrode membrane comprising a polymeric matrix wherein the matrix comprises:

an epoxy resin; and

a polyamide as an amine agent. See claim 1 and paragraph [0006] of No. 05-60724.

It would have been obvious to one with ordinary skill in the art at the time of the invention to use the chloride selective membrane of No. 05-60724 in the invention of Craig because as taught by No. 05-60724 the susceptibility of the sensor to interference from lipophilc ions and hydrophilic ions can be adjusted as desired (paragraphs [0012]-[0014]) and as taught by Craig, "A variety of ion selective membrane paste composition may be used to form the conventional sensor membrane layer 16 ..." (col. 03:52-54).

No. 05-60724 does not mention providing the agent in stoichiometric excess. However, No. 05-60724 does teach that varying the ratio of polythiol epoxy resin to polyamide epoxy resin in the polymeric matrix will alter the ion selectivity. In particular, a larger presence of polyamide epoxy resin than polythiol epoxy resin will make the polymeric matrix less susceptible to interference from hydrophilic ions. A larger presence of polythiol epoxy resin than polyamide epoxy resin will make the polymeric matrix less susceptible to interference from lipophilc ions. See paragraphs [0012] to

[0014]. Thus, providing a much larger relative amount of polyamide epoxy resin to polythiol epoxy resin and thus a stoichiometric excess of agent is just a matter of optimizing the polymeric matrix to be selective against lipohilic ions.

Alternatively, It would have been obvious to one with ordinary skill in the art at the time of a stoichiometric excess of agent because as taught by Ghahramani, which discloses a membrane for use in chloride-sensitive electrodes, the membrane comprising an epoxy resin with an amino curing agent, this will result in a high degree of selectivity. See the abstract; col. 03:23-30 and col. 04:61-67 in Ghahramani.

## Allowable Subject Matter

- 5. Claims 10, 13-15, 20, and 21 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- 6. The following is a statement of reasons for the indication of allowable subject matter:

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- a) Claim 10: the combination of limitations requires the polymer matrix to further comprise an adhesion promoter selected from the group consisting of clays, silica, silicates, and mixtures thereof. Neither No. 05-60724 nor Ghahramani discloses including any of these substances in the polymer matrix. The Written Opinion for PCT/DK2004/000496 merely states, "the use of an adhesion promoter does not seem inventive." Note that claim 9 in PCT/DK2004/000496 corresponds to claim 10 in the instant application.
- b) Claim 13: the combination of limitations requires the amine agent to be an amidoamine. No. 05-60724 only recites polyamide and Ghahramani just recites using "amino compound as a curing agent." Note that claim 13 in the instant application does not correspond to any of claims 1-15 in Application PCT/DK2004/000496 (WO 2005/005975 A1).
- c) Claims 14 and 15 depend from allowable claim 13.
- d) Claims 20 and 21: each of the combination of limitations requires the step of "heating the substrate containing dispensed chloride selective material to obtain chloride selective membrane." In No. 05-60724 all heating is performed before the material contacts the substrate. The material is cooled before it is adhered to the substrate. See paragraph [0025]. It would not have been obvious to heat the substrate as claimed because membrane must be formed a flat substrate first

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since the electrode cell substrate has an opening over which the membrane is to

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be placed. See Figure 1.

7. Any inquiry concerning this communication or earlier communications from the

examiner should be directed to ALEX NOGUEROLA whose telephone number is (571) 272-

1343. The examiner can normally be reached on M-F 8:30 - 5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, NAM NGUYEN can be reached on (571) 272-1342. The fax phone number for the

organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

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applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Alex Noguerola

Primary Examiner

AU 1753

November 25, 2006